## CLAIMS

- 1. A fluorine containing cyclic compound represented by the following general formula (1):
- 5 [Chemical Formula 30]

$$\begin{array}{c|cccc}
O & CF_3 \\
& OH \\
R_1a & CF_3 \\
R_2 & R_3
\end{array}$$
(1)

in the general formula (1), R1a is a C<sub>1</sub>·C<sub>25</sub> cyclic alkyl group, cyclic alkenyl group or cyclic alkynyl group; each of R2 and R3 is independently a hydrogen atom, a halogen atom, or a C<sub>1</sub>·C<sub>25</sub> straight-chain, branched or cyclic alkyl group; and each of R1a, R2 and R3 may contain fluorine atom, oxygen atom, sulfur atom, nitrogen atom or an atomic group containing a carbon-carbon double bond.

 A fluorine containing cyclic compound represented by the following general formula (2):

[Chemical Formula 31]

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$$R_4$$
 OH  $CF_3$  OH  $CF_3$  OH  $CF_3$   $CF_3$   $CF_3$  (2)

in the general formula (2), R1a is a C<sub>1</sub>·C<sub>25</sub> cyclic alkyl group, cyclic alkenyl group or cyclic alkynyl group; each of R2 to R4 is independently a hydrogen atom, a halogen atom, or a C<sub>1</sub>·C<sub>25</sub> straight chain, branched or cyclic

alkyl group; and each of R1a and R2 to R4 may contain fluorine atom, oxygen atom, sulfur atom, nitrogen atom or an atomic group containing a carbon-carbon double bond.

5 3. A fluorine-containing cyclic compound represented by the following general formula (3):

[Chemical Formula 32]

$$R_{6}$$
 $R_{7}$ 
 $R_{8}$ 
 $R_{8}$ 
 $CF_{3}$ 
 $R_{1}b$ 
 $R_{2}$ 
 $R_{3}$ 
 $R_{3}$ 

in the general formula (3), R1b is a  $C_1$ - $C_{25}$  cyclic alkyl group, cyclic alkenyl group, cyclic alkynyl group, aryl group, or heterocyclic group, and may contain fluorine atom, oxygen atom, sulfur atom, nitrogen atom or an atomic group containing a carbon-carbon double bond; each of R2 to R7 is independently a hydrogen atom, a halogen atom, or a  $C_1$ - $C_{25}$  straight-chain, branched or cyclic alkyl group, and may contain fluorine atom, oxygen atom, sulfur atom, nitrogen atom or an atomic group containing a carbon-carbon double bond; and R8 is a carbonyl group or methylene group, or a single bond.

- 4. A fluorine-containing cyclic compound represented by the following general formula (4):
- 20 [Chemical Formula 33]

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$$R_{14}$$
 $R_{12}$ 
 $R_{10}$ 
 $R$ 

in the general formula (4), each of R2, R3 and R9 to R15 is independently a hydrogen atom, a halogen atom, or a  $C_1 \cdot C_{25}$  straight-chain, branched or cyclic alkyl group, and may contain fluorine atom, oxygen atom, sulfur atom, or nitrogen atom; R10 and R11 or R12 and R13 may be bonded together to form a ring; in such case, it is an  $C_1 \cdot C_{25}$  alkylene group that may contain oxygen, sulfur, nitrogen or hetero atom; and "a" is 0 or 1, "b" is an integer of 0-2, and "c" is an integer of 0-2.

10 5. A fluorine-containing cyclic compound represented by the following general formula (5):

[Chemical Formula 34]

in the general formula (5), each of R2 to R4 and R9 to R15 is independently a hydrogen atom, a halogen atom, or a  $C_1 \cdot C_{25}$  straight-chain, branched or cyclic alkyl group, and may contain fluorine atom, oxygen atom, sulfur atom, or nitrogen atom; R10 and R11 or R12 and R13 may be bonded together to form a ring; in such case, it is an  $C_1 \cdot C_{25}$  alkylene group that may contain oxygen, sulfur, nitrogen or hetero atom; and "a" is 0 or 1, "b" is an integer of 0.2, and "c" is an integer of 0.2.

 A fluorine-containing cyclic compound represented by the following general formula (6):

[Chemical Formula 35]

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$$R_{6}$$
 $R_{7}$ 
 $R_{8}$ 
 $R_{12}$ 
 $R_{10}$ 
 $R_{4}$ 
 $CF_{3}$ 
 $R_{15}$ 
 $R_{13}$ 
 $R_{11}$ 
 $R_{11}$ 
 $R_{12}$ 
 $R_{10}$ 
 $R_{2}$ 
 $R_{3}$ 
 $R_{3}$ 
 $R_{11}$ 
 $R_{13}$ 
 $R_{11}$ 

in the general formula (6), each of R2 to R7 and R9 to R15 is independently a hydrogen atom, a halogen atom, or a  $C_1$ - $C_{25}$  straight-chain, branched or cyclic alkyl group, and may contain fluorine atom, oxygen atom,

sulfur atom, or nitrogen atom; R8 is a carbonyl group or methylene group or a single bond; R10 and R11, R12 and R13, or R14 and R15 may be bonded together to form a ring; in such case, it is an C<sub>1</sub>·C<sub>25</sub> alkylene group that may contain oxygen, sulfur, nitrogen or hetero atom; and "a" is 0 or 1, "b" is an integer of 0·2, and "c" is an integer of 0·2.

7. A fluorine containing cyclic compound represented by the following general formula (7):

[Chemical Formula 36]

$$\begin{array}{c|c}
O & CF_3 \\
OH \\
R_2 & R_3 & CF_3
\end{array}$$

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in the general formula (7), each of R2 and R3 is independently a hydrogen atom, a halogen atom, or a  $C_1 \cdot C_{25}$  straight-chain, branched or cyclic alkyl group, and may contain fluorine atom, oxygen atom, sulfur atom, or nitrogen atom.

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8. A fluorine-containing cyclic compound represented by the following general formula (8):

[Chemical Formula 37]

in the general formula (8), each of R2 to R4 is independently a hydrogen atom, a halogen atom, or a C<sub>1</sub>·C<sub>25</sub> straight chain, branched or cyclic alkyl group, and may contain fluorine atom, oxygen atom, sulfur atom, or nitrogen atom.

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 A fluorine-containing cyclic compound represented by the following general formula (9):

[Chemical Formula 38]

$$R_6$$
 $R_7$ 
 $R_8$ 
 $R_4$ 
 $O$ 
 $CF_3$ 
 $OH$ 
 $CF_3$ 
 $CF_3$ 
 $(9)$ 

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in the general formula (9), each of R2 to R7 is independently a hydrogen atom, a halogen atom, or a  $C_1$ - $C_{25}$  straight-chain, branched or cyclic alkyl group, and may contain fluorine atom, oxygen atom, sulfur atom, or nitrogen atom; and R8 is a carbonyl group or methylene group or a single bond.

15 10. mol

10. A fluorine containing polymer compound having a weight average molecular weight of 1,000 to 1,000,000, which is characterized in comprising a repeating unit represented by the following general formula (10):

[Chemical Formula 39]

$$\begin{array}{c}
R_6 \\
R_7 \\
R_8 \\
O \\
CF_3 \\
CF_3 \\
CF_3 \\
CF_3
\end{array}$$
(10)

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in the general formula (10), R1b and R2 to R8 are defined as in claim 3.

11. A fluorine-containing polymer compound having a weight average molecular weight of 1,000 to 1,000,000, which is characterized in comprising a repeating unit represented by the following general formula (11):

[Chemical Formula 40]

$$R_{14}$$
 $R_{12}$ 
 $R_{10}$ 
 $R_{4}$ 
 $R_{2}$ 
 $R_{10}$ 
 $R_{2}$ 
 $R_{3}$ 
 $R_{13}$ 
 $R_{11}$ 
 $R_{11}$ 
 $R_{11}$ 
 $R_{11}$ 
 $R_{11}$ 
 $R_{12}$ 
 $R_{13}$ 
 $R_{11}$ 
 $R_{11}$ 

in the general formula (11), R2 to R15 and a, b and c are defined as in claim 6

12. A fluorine-containing polymer compound having a weight average molecular weight of 1,000 to 1,000,000, which is characterized in comprising a repeating unit represented by the following general formula (12):

[Chemical Formula 41]

$$R_{7}$$
 $R_{8}$ 
 $CF_{3}$ 
 $R_{3}$ 
 $R_{4}$ 
 $R_{12}$ 

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in the general formula (12), R2 to R8 are defined as in claim 9.

13. A fluorine containing polymer compound having a weight average molecular weight of 1,000 to 1,000,000, which is characterized in comprising a repeating unit represented by the following general formula (13):

[Chemical Formula 42]

$$R_{15}R_{14}$$
 $R_{13}$ 
 $R_{12}$ 
 $R_{11}$ 
 $R_{10}$ 
 $R_{9}$ 
 $R_{2}$ 
 $R_{3}$ 
 $R_{3}$ 
 $R_{3}$ 
 $R_{3}$ 
 $R_{4}$ 
 $R_{5}$ 
 $R_{10}$ 
 $R_{$ 

in the general formula (13), R2, R3 and R9 to R15 and a, b and c are defined as in claim 4.

5 14. A fluorine containing polymer compound having a weight average molecular weight of 1,000 to 1,000,000, which is characterized in comprising a repeating unit represented by the following general formula (14):

[Chemical Formula 43]

$$R_{15}R_{14}$$
 $R_{13}$ 
 $R_{12}$ 
 $R_{10}$ 
 $R_{9}$ 
 $R_{2}$ 
 $R_{4}$ 
 $R_{3}$ 
 $R_{3}$ 
 $R_{3}$ 
 $R_{3}$ 
 $R_{4}$ 
 $R_{10}$ 
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 $R_{15}$ 
 $R_{10}$ 
 $R_{$ 

in the general formula (14), R2 to R4 and R9 to R15 and a, b and c are defined as in claim 5.

5 15. A fluorine containing polymer compound having a weight average molecular weight of 1,000 to 1,000,000, which is characterized in comprising a repeating unit represented by the following general formula (15): [Chemical Formula 44]

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in the general formula (15), R2 and R3 are defined as in claim 7.

16. A fluorine containing polymer compound having a weight average molecular weight of 1,000 to 1,000,000, which is characterized in comprising a repeating unit represented by the following general formula (16):

[Chemical Formula 45]

in the general formula (16), R2 to R4 are defined as in claim 8.

17. A fluorine-containing polymer compound having a weight average molecular weight of 1,000 to 1,000,000 according to claims 13 to 16, which is characterized in comprising a repeating unit represented by the following general formula (17):

[Chemical Formula 46]

in the general formula (17), R16 is a hydrogen atom, or a  $C_1$ - $C_{25}$  straight-chain, branched or cyclic alkyl group, and may contain fluorine atom, oxygen atom, sulfur atom, nitrogen atom, hydroxyl group or hexafluorocarbinol group.

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18. A fluorine containing polymer compound according to any one of claims 10·17, which is characterized in comprising a repeating unit having an acidlabile group.

10 19. A fluorine containing cyclic compound or fluorine containing polymer compound according to any one of claims 1·18, which is characterized in that hydroxy groups contained in the molecule are partially or entirely protected with protecting groups.

- 15 20. A resist material characterized in comprising a fluorine containing polymer compound according to any one of claims 10-19.
  - 21. A chemically amplified resist material characterized in comprising a resist material according to claim 20 and a photoacid generator.

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- 22. A pattern forming process characterized in comprising at least the steps of applying a resist material according to claim 20 or 21 to a substrate; subjecting the substrate to a heat treatment; conducting an exposure, using a high-energy ray of a wavelength of 300nm or less or an electron beam, through a photomask; subjecting the exposed resist film to a heat treatment; and conducting a development treatment.
- 23. A pattern forming process according to claim 22, wherein the highenergy ray used is F<sub>2</sub> excimer laser, ArF excimer laser, KrF excimer laser 30 or soft X-ray.